

ELECTRONIC INFORMATION DISCLOSURE STATEMENT

Electronic Version v18

Stylesheet Version v18.0

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| Title of Invention | Method of Forming Silicon Dioxide Using Siloxane |
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Application Number : 10/782094



Confirmation Number: 4756

First Named Applicant: Jae-Eun Park

Attorney Docket Number: SAM-0483

Art Unit:

Examiner:

Search string: (6664156 or 5037514 or 6534395 or 20020164890 or 20030015764 or 20020047151).pn

US Patent Documents

Note: Applicant is not required to submit a paper copy of cited US Patent Documents

| init | Cite.No. | Patent No. | Date | Patentee | Kind | Class | Subclass |
|------|----------|------------|------------|-------------------|------|-------|----------|
| | 1 | 6664156 | 2003-12-16 | Ang, et al. | | | |
| | 2 | 5037514 | 1991-08-06 | Yamazaki | | | |
| | 3 | 6534395 | 2003-03-18 | Werkhoven, et al. | | | |

US Published Applications

Note: Applicant is not required to submit a paper copy of cited US Published Applications

| init | Cite.No. | Pub. No. | Date | Applicant | Kind | Class | Subclass |
|------|----------|-------------|------------|---------------------|------|-------|----------|
| | 1 | 20020164890 | 2002-11-17 | Kwan, et al. | | | |
| | 2 | 20030015764 | 2003-01-23 | Raaijmakers, et al. | | | |
| | 3 | 20020047151 | 2002-04-25 | Kim, et al. | | | |

Remarks

Note: Remarks are not for responding to an office action.

part 1 of 1

Signature

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|---------------|------|
| Examiner Name | Date |
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